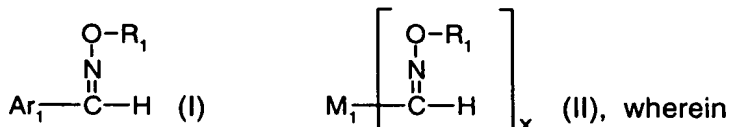


Abstract

Photosensitive compositions comprising

- (A) an alkali soluble compound;
- (B) at least one compound of formula I or II



R₁ inter alia is C₄-C₉cycloalkanoyl, C₃-C₁₂alkenoyl, or benzoyl which is unsubstituted or substituted; Ar₁ is either C₆-C₂₀aryl or C₆-C₂₀aryloyl each of which is unsubstituted or substituted; x is 2 or 3; M₁ when x is 2, inter alia is a group phenylene or naphthylene, each of which optionally is substituted i.a. by OR₃, SR₄ or NR₅R₆; or M₁, when x is 3, is a trivalent group, optionally substituted; R₃ is for example hydrogen or C₁-C₁₂alkyl; C₂-C₆alkyl which is for example substituted by -OH, -SH, -CN, C₃-C₆alkenoxy, or -OCH₂CH₂CN; R₄ is for example hydrogen, C₁-C₁₂alkyl, C₃-C₁₂alkenyl, cyclohexyl, or phenyl which is unsubstituted or substituted; R₅ and R₆ independently of each other inter alia are hydrogen, C₁-C₁₂alkyl, C₂-C₄hydroxyalkyl, C₂-C₁₀alkoxyalkyl, C₃-C₅alkenyl, C₃-C₈cycloalkyl, phenyl-C₁-C₃alkyl, C₁-C₄alkanoyl, C₃-C₆alkenoyl, benzoyl or phenyl which is unsubstituted or substituted; and

- (C) a photopolymerizable compound;

exhibit an unexpectedly good performance, in particular in photoresist technology.